### Nonlinear optics at the nanoscale



Louisiana State University Baton Rouge, LA, 28 April 2014



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## Outline





supercontinuum generation

optical logic gates

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#### Nature, 426, 816 (2003)







20 µm

#### Poynting vector profile for 200-nm nanowire













minimum bending radius: 5.6 μm



#### aerogel

#### 420 nm

420 nm

Nanoletters, 5, 259 (2005)



in

out

Nanoletters, 5, 259 (2005)



Nanoletters, 5, 259 (2005)

Points to keep in mind:

- low-loss guiding
- convenient evanescent coupling
- attached to ordinary fiber



supercontinuum generation

optical logic gates











#### strong confinement $\longrightarrow$ high intensity



mode field diameter ( $\lambda$  = 800 nm)



M.A. Foster, et al., Optics Express, 12, 2880 (2004)

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M.A. Foster, et al., Optics Express, 12, 2880 (2004)
#### nonlinear parameter



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dispersion important!

### dispersion:

- modal dispersion
- material dispersion
- waveguide dispersion
- nonlinear dispersion

### waveguide dispersion



### waveguide dispersion



### waveguide dispersion



### waveguide dispersion



### waveguide dispersion



### waveguide dispersion



### waveguide dispersion



#### waveguide dispersion



### waveguide dispersion



### waveguide dispersion



#### nanowire continuum generation



#### nanowire continuum generation



#### nanowire continuum generation



#### nanowire continuum generation



#### nanowire continuum generation



#### nanowire continuum generation



#### nanowire continuum generation



#### energy in nanowire < 100 pJ!

- picojoule nonlinear optics
- optimum diameter for silica 500–600 nm
- low dispersion



• manipulating light at the nanoscale

supercontinuum generation

optical logic gates











#### output = transmitted cw + ccw power



### input electric field amplitude $E_{in}$



coupling parameter:  $\rho$ 



### phase accumulation over path length of loop L



### coupling parameter: $\rho$



#### output is sum of transmitted cw and ccw



# Manipulating light at the nanoscale

accumulated phase:

$$\phi = k_o n$$

# Manipulating light at the nanoscale

### accumulated phase:

$$\phi = k_o n$$

#### nonlinear index:

$$n = n_o + n_2 I = n_o + n_2 \frac{P_i}{A_{eff}}$$
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$$\phi = k_o n$$

#### nonlinear index:

$$n = n_o + n_2 I = n_o + n_2 \frac{P_i}{A_{eff}}$$

nonlinear parameter:

$$\gamma = n_2 \frac{k_o}{A_{eff}}$$

#### power-dependent output:

$$\frac{E_{out}^2}{E_{in}^2} = 1 - 2\rho(1-\rho)\{1 + \cos[(1-2\rho)\gamma P_o L]\}$$

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#### for 50-50 coupler:

$$\rho = 0.5$$

#### power-dependent output:

$$\frac{E_{out}^2}{E_{in}^2} = 1 - 2\rho(1-\rho)\{1 + \cos[(1-2\rho)\gamma P_o L]\}$$

#### for 50-50 coupler:

$$\rho = 0.5$$

no transmission:

$$\frac{E_{out}^2}{E_{in}^2} = 0$$

when  $\rho \neq 0.5$ :



































#### for NAND gate need ouput with no input



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#### for NAND gate need ouput with no input



#### universal NAND gate



#### universal NAND gate



#### universal NAND gate



mesoporous silica

Sagnac loop



### output

#### mesoporous silica

Sagnac loop

#### very preliminary data



#### light-by-light modulation!

#### very preliminary data



#### very preliminary data





need a different approach!
need a different approach!

lithographic fabrication

need a different approach!

- lithographic fabrication
- greater index

need a different approach!

- lithographic fabrication
- greater index
- greater nonlinearity





TiO <sub>2</sub> properties		
large nonlinearity	30x silica	
high index of refraction	2.4	
wide bandgap	3.1 eV	
low two-photon absorption	> 800 nm	
effective nonlinearity	50,000 W <sup>-1</sup> km <sup>-1</sup>	

#### reactive sputtering of titanium with oxygen

#### begin with silicon wafer with thermal oxide

thermal oxide

Si wafer

#### deposit titania using reactive sputtering

titania film

thermal oxide

Si wafer

#### spin on e-beam resist

e-beam resist titania film thermal oxide

Si wafer

#### write pattern using e-beam



#### develop to remove exposed regions



#### deposit thin metal film



#### dissolve resist, lift off metal film



Si wafer

#### reactive ion etch through titania film



thermal oxide

Si wafer





Si wafer



















the second second second second second



















#### **Summary**

- several nanodevices demonstrated
- large γ permits miniature Sagnac loops
- switching energy ≈ 100 pJ







**Funding:** 

Harvard Center for Imaging and Mesoscopic Structures National Science Foundation National Natural Science Foundation of China

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